L	Hits	Search Text	DB	Time stamp
Number		1400/040 050 050 000 000	110000	2002/10/07
1	0	438/240,250,253,393,399.pn. and (Ta or	USPAT;	2003/10/27
		tantalum) and CVD and (capacitor) and	US-PGPUB;	15:37
		(precursor) and (source adj gas) and	EPO; JPO;	
		(oxygen) and (dielectric) and (tantalum	DERWENT	
-		adj pentamethoxide or tantalum adj	1	
		pentaethoxide)	iicDam.	2003/10/27
2	0	438/240, 250, 253, 393, 399.pn. and (Ta or	USPAT;	
		tantalum) and CVD and (capacitor) and	US-PGPUB; EPO; JPO;	15:38
		(precursor) and (source adj gas) and (oxygen) and (dielectric) and (tantalum	DERWENT	
		adj pentamethoxide or tantalum adj	DEKWENI	
		pentaethoxide)		
_	15673	(Ta or tantalum) and CVD	USPAT;	2003/05/27
	13073	(14 of cancaram) and orb	US-PGPUB;	09:04
			EPO; JPO;	
			DERWENT	
_	897	(Ta or tantalum) and CVD and (capacitor)	USPAT;	2003/05/26
		and (precursor)	US-PGPUB;	15:23
		(1)	EPO; JPO;	
			DERWENT	
_	102	(Ta or tantalum) and CVD and (capacitor)	USPAT;	2003/05/26
		and (precursor) and (source adj gas) and	US-PGPUB;	15:27
		(oxygen)	EPO; JPO;	
ł			DERWENT	
-	96	(Ta or tantalum) and CVD and (capacitor)	USPAT;	2003/05/30
		and (precursor) and (source adj gas) and	US-PGPUB;	16:08
		(oxygen) and (dielectric)	EPO; JPO;	
			DERWENT	/
-	30822	(Ta or tantalum) and CVD and (capacitor)	USPAT;	2003/05/26
		and (precursor) and (source adj gas) and	US-PGPUB;	15:28
		(oxygen) and (dielectric) (lower adj	EPO; JPO;	1
	2.1	electrode)	DERWENT	2002/05/26
-	21	(Ta or tantalum) and CVD and (capacitor)	USPAT; US-PGPUB;	2003/05/26 15:28
		and (precursor) and (source adj gas) and (oxygen) and (dielectric) and (lower adj	EPO; JPO;	13.28
		(oxygen) and (drefectife) and (fower adj electrode)	DERWENT	
l _	12	(Ta or tantalum) and CVD and (capacitor)	USPAT;	2003/05/27
	12	and (precursor) and (source adj gas) and	US-PGPUB;	16:44
		(oxygen) and (dielectric) and (lower adj	EPO; JPO;	
·		electrode) and (upper adj electrode)	DERWENT	
_	12	(Ta or tantalum) and CVD and (capacitor)	USPAT;	2003/05/26
		and (precursor) and (source adj gas) and	US-PGPUB;	15:32
		(oxygen) and (dielectric) and (lower adj	EPO; JPO;	
		electrode) and (upper adj electrode) and	DERWENT	
		(substrate)		
-	0	6207489.pn. and purging	USPAT;	2003/05/27
			US-PGPUB;	09:06
			EPO; JPO;	
	_	6307400	DERWENT	2002/05/20
-	2	6207489.pn.	USPAT;	2003/05/28
			US-PGPUB;	13:38
	1		EPO; JPO; DERWENT	
l _	2	20020100959.pn.	USPAT;	2003/05/27
l ⁻	2	20020100303.pm.	US-PGPUB;	09:25
			EPO; JPO;	03.20
			DERWENT	
_	0	20020100959.pn. and (purge or purging)	USPAT;	2003/05/27
			US-PGPUB;	09:26
			EPO; JPO;	
			DERWENT	
-	0	20020100959.pn. and (purge or purging or	USPAT;	2003/05/27
		exhaust)	US-PGPUB;	09:27
			EPO; JPO;	
			DERWENT	
-	0	6207489.pn. and (purge or purging or	USPAT;	2003/05/27
		exhaust)	US-PGPUB;	09:28
1			EPO; JPO;	
			DERWENT	

_	0	6218260.pn. and (purge or purging or exhaust)	USPAT; US-PGPUB; EPO; JPO;	2003/05/27 09:29
			DERWENT	
	2	20020006708.pn. and (purge or purging or	USPAT;	2003/05/27
] - [exhaust)	US-PGPUB;	17:50
		exitause	EPO; JPO;	2,700
			DERWENT	
l <u> </u>	9	(Ta or tantalum) and CVD and (capacitor)	USPAT;	2003/05/27
		and (precursor) and (source adj gas) and	US-PGPUB;	16:57
		(oxygen) and (dielectric) and (lower adj	EPO; JPO;	
		electrode) and (upper adj electrode) and	DERWENT	
		(Ru or Pt or Ir.)		
_	1	6376299.pn. and (Ru or Pt or Ir.)	USPAT;	2003/05/27
		•	US-PGPUB;	17:00
			EPO; JPO;	
			DERWENT	
-	2	6482740.pn. and (Ru or Pt or Ir.)	USPAT;	2003/05/27
	i		US-PGPUB;	17:08
ĺ	1	·	EPO; JPO;	
		5075000 J. /B	DERWENT	2002/05/27
-	1	6376299.pn. and (Ru or Pt or Ir.)	USPAT; US-PGPUB;	2003/05/27 17:17
[.			EPO; JPO;	11.11
			DERWENT	
_	0	6376299.pn. and (Ru or Pt or Ir.) and	USPAT;	2003/05/27
_		(purge or purging or exhaust)	US-PGPUB;	17:16
		(Family or Family or assumption)	EPO; JPO;	
			DERWENT	
-	1	20020006708.pn. and (Ru or Pt or Ir.)	USPAT;	2003/05/28
		•	US-PGPUB;	12:01
			EPO; JPO;	
			DERWENT	
-	1	20020100959.pn. and (Ru or Pt or Ir.)	USPAT;	2003/05/27
			US-PGPUB;	17:28
1			EPO; JPO; DERWENT	
	0	20020100959.pn. and (Ru or Pt or Ir.) and	USPAT;	2003/05/27
-		(purge or purging)	US-PGPUB;	17:29
		(purge or purgray)	EPO; JPO;	
			DERWENT	
_	1	20020100959.pn. and (Ru or Pt or Ir.) and	USPAT;	2003/05/27
	_	(flow adj rate)	US-PGPUB;	17:30
			EPO; JPO;	
			DERWENT	
-	0	6372598.pn. and (Ru or Pt or Ir.) and	USPAT;	2003/05/27
		(flow adj rate)	US-PGPUB;	17:30
			EPO; JPO;	
		(272500 mm and /Du cm D+ cm Tm \	DERWENT USPAT;	2003/05/27
-	1	6372598.pn. and (Ru or Pt or Ir.)	US-PGPUB;	17:31
			EPO; JPO;	-,,,,,
			DERWENT	
_	1	20020006708.pn. and (titanium adj nitride	USPAT;	2003/05/27
	1	or tantalum adj nitride or tungsten adj	US-PGPUB;	17:57
1		nitride)	EPO; JPO;	
		·	DERWENT	
-	1	20020006708.pn. and (titanium adj nitride	USPAT;	2003/05/27
		or tantalum adj nitride or tungsten adj	US-PGPUB;	17:58
		nitride) and (precursor)	EPO; JPO;	
	-	20020006708 pp. and /Pu on Pt on Tr \ and	DERWENT USPAT;	2003/05/28
-	1	20020006708.pn. and (Ru or Pt or Ir.) and (bottom or lower adj electrode)	US-PGPUB;	12:13
		(200000 of 10mol day electione)	EPO; JPO;	
			DERWENT	
-	1	20020006708.pn. and (argon or nitrogen)	USPAT;	2003/09/17
			US-PGPUB;	15:54
1	1		EPO; JPO;	
1	l		DERWENT	

Page 2

-	0	20020006708.pn. and (sccm)	USPAT;	2003/05/28
İ			US-PGPUB;	12:16
			EPO; JPO;	
			DERWENT	
-	1	20020006708.pn. and (flow)	USPAT;	2003/05/28
			US-PGPUB;	13:27
			EPO; JPO;	
			DERWENT	/
-	0	20020006708.pn. and (flow adj rate)	USPAT;	2003/05/28
			US-PGPUB;	13:27
			EPO; JPO;	
	_		DERWENT	/
-	0	20020006708.pn. and (sccm)	USPAT;	2003/05/28
			US-PGPUB;	13:28
			EPO; JPO;	
		200000000000000000000000000000000000000	DERWENT	2003/05/28
-	1	20020006708.pn. and (flow)	USPAT;	1
			US-PGPUB;	13:32
	i		EPO; JPO;	
		1 / 4 4 4 4 4 4 4 4 4	DERWENT	1 2002 (05 /29
-	0	20020006708.pn. and (cubic adj	USPAT;	2003/05/28
		centimeters)	US-PGPUB;	13:33
			EPO; JPO;	
1		C207480 mm	DERWENT	2003/05/28
-	2	6207489.pn.	USPAT; US-PGPUB;	13:38
Ì				13:30
	1		EPO; JPO; DERWENT	
	1	6207480 mm and flow	USPAT;	2003/05/28
-	1	6207489.pn. and flow	US-PGPUB;	13:41
			EPO; JPO;	13.41
		,	DERWENT	
	0	(207490 nn and agam	USPAT;	2003/05/28
-	"	6207489.pn. and sccm	US-PGPUB;	13:42
			EPO; JPO;	13.42
			DERWENT	
	1 1	6207489.pn. and flow adj rate	USPAT;	2003/05/28
_	1	6207489.pn. and flow adj face	US-PGPUB;	13:42
			EPO; JPO;	13.42
			DERWENT	
	96	438/240,250,253,393,399(Ta or tantalum)	USPAT;	2003/09/23
		and CVD and (capacitor) and (precursor)	US-PGPUB;	15:45
		and (source adj gas) and (oxygen) and	EPO; JPO;	101.10
		(dielectric)	DERWENT	
_	1	20020006708.pn. and (chemical adj vapor	USPAT;	2003/09/17
	*	adj deposition)	US-PGPUB;	16:58
		and appropriate	EPO; JPO;	
			DERWENT	
_	156	atomic adj layer adj deposition and	USPAT;	2003/09/17
		(atomic adj layer adj epitax\$3)	US-PGPUB;	17:24
		,	EPO; JPO;	į l
			DERWENT	
-	0	(atomic adj layer adj deposition and	USPAT;	2003/09/17
		(atomic adj layer adj epitax\$3)) near	US-PGPUB;	17:28
		dielectric adj insulat\$3	EPO; JPO;	
		-	DERWENT	
-	0	(atomic adj layer adj deposition and	USPAT;	2003/09/17
		(atomic adj layer adj epitax\$3)) with	US-PGPUB;	17:28
		dielectric adj insulat\$3	EPO; JPO;	
	1	-	DERWENT	
-	0	(atomic adj layer adj deposition and	USPAT;	2003/09/17
		(atomic adj layer adj epitax\$3)) near12	US-PGPUB;	17:29
		dielectric adj insulat\$3	EPO; JPO;	
	-	<u>-</u>	DERWENT	
-	0	atomic adj layer adj deposition and	USPAT;	2003/09/17
		atomic adj layer adj epitax\$3 and	US-PGPUB;	17:30
		dielectric adj insulat\$3 and	EPO; JPO;	
		international adj business adj machines	DERWENT	
-	6	atomic adj layer adj deposition and	USPAT;	2003/09/17
		atomic adj layer adj epitax\$3 and	US-PGPUB;	19:06
		dielectric adj insulat\$3	EPO; JPO;	Į l
	l		DERWENT	

-	1	6203613.pn. and CVD	USPAT;	2003/09/17
			US-PGPUB;	19:09
İ			EPO; JPO;	
İ			DERWENT	
-	0	6203613.pn. and compacitor	USPAT;	2003/09/17
			US-PGPUB;	19:10
			EPO; JPO;	
			DERWENT	
_	2	6203613.pn. and capacitor	USPAT;	2003/09/17
	_		US-PGPUB;	19:10
			EPO; JPO;	
			DERWENT	
_	1	20020006708.pn. and Ru	USPAT;	2003/09/22
	•		US-PGPUB;	16:28
			EPO; JPO;	
			DERWENT	
_	ا م	6207489.pn. and (tantalum adj	USPAT;	2003/09/23
		pentamethoxide)	US-PGPUB;	10:48
		percamethoxide/	EPO; JPO;	1
]			DERWENT	1
1_	2	(tantalum adj pentamethoxide) and	USPAT;	2003/09/23
-		capacitor	US-PGPUB;	12:14
		Capacitoi	EPO; JPO;	
			DERWENT	
	o	tantalum adj pentamethoxide) and	USPAT;	2003/09/23
-	0		US-PGPUB;	12:18
		capacitor and precursor	EPO; JPO;	12.10
			DERWENT	
	20	/		2003/09/23
~	38	(tantalum adj ethylate) and capacitor and	USPAT;	
		electrode	US-PGPUB;	12:20
			EPO; JPO;	
			DERWENT	
-	23		USPAT;	2003/09/23
		electrode and precursor	US-PGPUB;	12:20
			EPO; JPO;	
			DERWENT	
-	23	(tantalum adj ethylate) and capacitor and	USPAT;	2003/09/23
		electrode and precursor	US-PGPUB;	12:21
			EPO; JPO;	
			DERWENT	
-	0	6110531.pn. and (tantalum adj	USPAT;	2003/09/23
1	,	pentamethoxide) and capacitor and	US-PGPUB;	12:42
		electrode	EPO; JPO;	
			DERWENT	
-	0		USPAT;	2003/09/23
		pentamethoxide)	US-PGPUB;	12:42
		·	EPO; JPO;	
			DERWENT	
-	0	5601869.pn. and (tantalum adj	USPAT;	2003/09/23
	1	pentamethoxide)	US-PGPUB;	12:43
	1	· ·	EPO; JPO;	
	1		DERWENT	
-	0	jp-05243524-\$.did. and (tantalum adj	USPAT;	2003/09/23
	1	pentamethoxide)	US-PGPUB;	12:45
		*	EPO; JPO;	
	1		DERWENT	
_	0	(tantalum adj pentamethoxide) and	USPAT;	2003/09/23
	1	capacitor and electrode	US-PGPUB;	14:19
	1		EPO; JPO;	·
	1		DERWENT	
_	0	438/240,250,253,393,399(Ta or tantalum)	USPAT;	2003/09/23
		and CVD and (capacitor) and (precursor)	US-PGPUB;	16:06
	1	and (source adj gas) and (oxygen) and	EPO; JPO;	
1	1	(dielectric) and (tantulum adj	DERWENT	
	1		DILMINI	
		pentamethoxide or tantulum adj		
	_	pentaethoxide)	HCDATT.	2003/09/23
-	0	438/240,250,253,393,399(Ta or tantalum)	USPAT;	15:51
		and CVD and (capacitor) and (precursor)	US-PGPUB;	13:31
		and (source adj gas) and (oxygen) and	EPO; JPO;	1
!		(dielectric) and ((tantulum adj	DERWENT	
1		pentamethoxide) or (tantulum adj		
		pentaethoxide))		

				0000/00/00
-	0	(Ta or tantalum) and CVD and (capacitor)	USPAT;	2003/09/23
		<pre>and (precursor) and (source adj gas) and (oxygen) and (dielectric) and ((tantulum)</pre>	US-PGPUB; EPO; JPO;	15:52
		adj pentamethoxide) or (tantulum adj	DERWENT	
		pentaethoxide))	DUNWENT	
_	1	(Ta or tantalum) and CVD and (capacitor)	USPAT;	2003/09/23
	_	and (precursor) and (source adj gas) and	US-PGPUB;	15:52
		(oxygen) and (dielectric) and ((tantalum	EPO; JPO;	i
		adj pentamethoxide) or (tantalum adj	DERWENT	
		<pre>pentaethoxide))</pre>		
-	0	438/240,250,253,393,396,399(Ta or	USPAT;	2003/09/23
		tantalum) and CVD and (capacitor) and	US-PGPUB;	16:08
1		(precursor) and (source adj gas) and	EPO; JPO; DERWENT	
Ĭ		(oxygen) and (dielectric) and (tantulum adj pentamethoxide or tantulum adj	DEKMENI	
İ		pentaethoxide)		
_) o		USPAT;	2003/10/23
		para in the second para in the s	US-PGPUB;	15:52
1			EPO; JPO;]
			DERWENT	
. -	0	5919963.pn. and (precursor or absorption)	USPAT;	2003/10/23
			US-PGPUB;	16:23
1			EPO; JPO; DERWENT	
1_	1	20020025628.pn. and purging	USPAT;	2003/10/24
-	1	20020023626.pii. and purgring	US-PGPUB;	11:45
			EPO; JPO;	
			DERWENT	
-	0	20020025628.pn. and ((titanium adj	USPAT;	2003/10/24
		nitride) or (tantalum adj nitride) or	US-PGPUB;	14:22
		(tungsten adj nitride))	EPO; JPO;	
	_		DERWENT	0003/10/04
-	0	6203613.pn. and ((titanium adj nitride)	USPAT; US-PGPUB;	2003/10/24
		or (tantalum adj nitride) or (tungsten adj nitride))	EPO; JPO;	14:50
		auj mittide,,	DERWENT	
_	1	6203613.pn. and (flow rate or sccm)	USPAT;	2003/10/24
	_	, and the same of	US-PGPUB;	17:53
	1		EPO; JPO;	
			DERWENT	/
-	1	20020025628.pn. and (flow rate or sccm)	USPAT;	2003/10/24
			US-PGPUB; EPO; JPO;	14:55
			DERWENT	
l <u>-</u>	147709	6203613.pn. and nitrogen or argon	USPAT;	2003/10/24
	1	02000200 0000 0000 0000 0000 0000 0000	US-PGPUB;	17:54
			EPO; JPO;	
			DERWENT	
-	1	6203613.pn. and (nitrogen or argon)	USPAT;	2003/10/24
			US-PGPUB;	17:56
			EPO; JPO; DERWENT	
_	1	6203613.pn. and (nitrogen or argon same	USPAT;	2003/10/24
		inert)	US-PGPUB;	17:56
			EPO; JPO;	
			DERWENT	
-	1	20020100959.pn. and precursor	USPAT;	2003/10/27
			US-PGPUB;	10:16
			EPO; JPO;	
1_	0	20020100959.pn. and absorption	DERWENT USPAT;	2003/10/27
1		20020100909.pit. and absorption	US-PGPUB;	10:18
			EPO; JPO;	
		·	DERWENT	
-	0	20020100959.pn. and (absorption or	USPAT;	2003/10/27
		absorb)	US-PGPUB;	10:19
	-		EPO; JPO;	
		6002612 414 /5 5 3 11 12 /3	DERWENT	2002/10/27
_	0	6203613.pn. and (tantalum adj chloride)	USPAT;	2003/10/27
			US-PGPUB; EPO; JPO;	12:14
			DERWENT	
	1	<u> </u>	1 22:/417147	